

SD210DE/214DE

N-CHANNEL LATERAL
DMOS SWITCH

PRODUCT SUMMARY

PART NUMBER	$V_{(BR)DS}$ Min (V)	$V_{(GS)th}$ Max (V)	$r_{DS(on)}$ Max (Ω)	C_{rss} Max (pF)	t_{ON} Max (ns)
SD210DE	30	1.5	45 @ $V_{GS}=10V$	0.5	2
SD214DE	20	1.5	45 @ $V_{GS}=10V$	0.5	2

Features

- Ultra-High Speed Switching— t_{ON} : 1ns
- Ultra-Low Reverse Capacitance: 0.2pF
- Low Guaranteed r_{DS} @5V
- Low Turn-On Threshold Voltage
- N-Channel Enhancement Mode

Benefits

- High-Speed System Performance
- Low Insertion Loss at High Frequencies
- Low Transfer Signal Loss
- Simple Driver Requirement
- Single Supply Operation

Applications

- Fast Analog Switch
- Fast Sample-and-Holds
- Pixel-Rate Switching
- DAC Deglitchers
- High-Speed Driver

Description

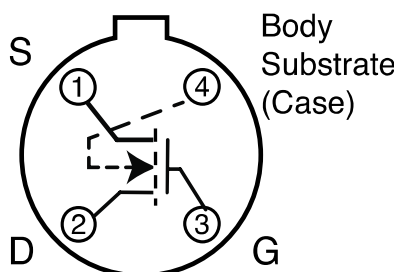
The SD210DE/214DE are enhancement-mode MOSFETs designed for high speed low-glitch switching in audio, video and high-frequency applications. The SD214DE is normally used for a ± 10 -V analog switching. These MOSFETs utilize lateral construction to achieve low capacitance and ultra-fast switching speeds. These MOSFETs do not have a gate protection Zener diode which

results in lower gate leakage and $\pm$ voltage capability from gate to substrate. A poly-silicon gate is featured for manufacturing reliability.

For similar products see: quad array—SD5000/5400 series, and Zener protected—SD211DE/SST211 series.

TOP VIEW

TO-206AF
(TO-72)



Absolute Maximum Ratings ($T_A = 25^\circ\text{C}$ unless otherwise noted)

Gate-Drain, Gate-Source Voltage	$\pm 40\text{V}$
Gate-Substrate Voltage	$\pm 30\text{V}$
Drain-Source Voltage	(SD210DE) 30V (SD214DE) 20V
Source-Drain Voltage	(SD210DE) 10V (SD214DE) 20V
Drain-Substrate Voltage	(SD210DE) 30V (SD214DE) 25V

Source-Substrate Voltage	(SD210DE) 15V (SD210DE) 25V
Drain Current	50mA
Lead Temperature (1/16" from case for 10 seconds)	300°C
Storage Temperature	-65 to 150°C
Operating Junction Temperature	-55 to 125°C
Power Dissipation*	300mW

Note:

* Derate $3\text{mW}/^\circ\text{C}$ above 25°C

Specifications^a

PARAMETER	SYMBOL ^b	TEST CONDITIONS ^b	TYP ^c	LIMITS				UNIT	
				SD210DE		SD214DE			
				Min	Max	Min	Max		
Static									
Drain - Source Breakdown Voltage	V _{(BR)DS}	V _{GS} = V _{BS} = 0V, I _D = 10 μA	35	30				V	
		V _{GS} = V _{BS} = -5V, I _D = 10 nA	30	10		20			
Source - Drain Breakdown Voltage	V _{(BR)SD}	V _{GD} = V _{BD} = -5V, I _S = 10 nA	22	10		20			
Drain - Substrate Breakdown Voltage	V _{(BR)DBO}	V _{GB} = 0V, I _D = 10 nA Source Open	35	15		25			
Source - Substrate Breakdown Voltage	V _{(BR)SBO}	V _{GB} = 0V, I _S = 10 μA Drain Open	35	15		25			
Drain – Source Leakage	I _{DS(off)}	V _{GS} = V _{BS} = -5V	V _{DS} = 10V	0.4		10		nA	
			V _{DS} = 20V	0.9			10		
Source - Drain Leakage	I _{SD(off)}	V _{GD} = V _{BD} = -5V	V _{SD} = 10V	0.5		10			
			V _{SD} = 20V	0.8			10		
Gate Leakage	I _{GBS}	V _{DB} = V _{SB} = 0V, V _{GB} = ±4 0V	0.001		0.1		0.1		
Threshold Voltage	V _{GS(th)}	V _{DS} = V _{GS} , I _D = 1 μA , V _{SB} = 0V	0.8	0.5	1.5	0.1	1.5	V	
Drain – Source On-Resistance	r _{DS(on)}	V _{SB} = 0V I _D = 1mA	V _{GS} = 5V	58		70		70	Ω
			V _{GS} = 10V	38		45		45	
			V _{GS} = 15V	30					
			V _{GS} = 20V	26					
			V _{GS} = 25V	24					

Specifications^a

PARAMETER	SYMBOL ^b	TEST CONDITIONS ^b	TYP ^c	LIMITS				UNIT
				SD210DE		SD214DE		
				Min	Max	Min	Max	
Dynamic								
Forward Transconductance	g _{fs}	V _{DS} = 10V, V _{SB} = 0V, I _D = 20mA, f = 1kHz	11	10		10		mS
	g _{os}		0.9					
Gate Node Capacitance	C _(GS+GD+GB)	V _{DS} = 10V, f = 1MHz V _{GS} = V _{BS} = -15V	2.5		3.5		3.5	pF
Drain Node Capacitance	C _(GD+DB)		1.1		1.5		1.5	
Source Node Capacitance	C _(GS+SB)		3.7		5.5		5.5	
Reverse Transfer Capacitance	C _{rss}		0.2		0.5		0.5	
Switching								
Turn-On Time	t _{D(on)}	V _{SB} = 0V, V _{IN0} to 5V, R _G = 25Ω V _{DD} = 5V, R _L = 680Ω	0.5		1		1	ns
	t _r		0.6		1		1	
Turn-Off Time	t _{D(off)}		2					
	t _f		6					

Notes:

- $T_A = 25^\circ C$ unless otherwise noted.
- B is the body (substrate) and $V_{(BR)}$ is breakdown voltage.
- Typical values are for DESIGN AID ONLY, not guaranteed nor subject to production testing.

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